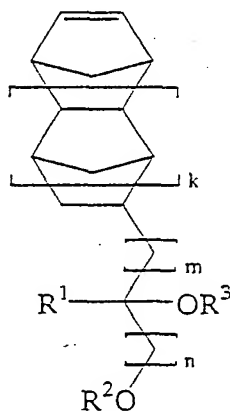


ABSTRACT

An ether compound of formula (1) is provided wherein
5 R^1 is H or C_{1-6} alkyl, R^2 is C_{1-6} alkyl, R^3 is H, C_{1-15} acyl or
 C_{1-15} alkoxy carbonyl which may be substituted with halogen
atoms, k is 0 or 1, m is from 0 to 3, and n is from 3 to 6.
The ether compound is polymerized to form a polymer having
improved reactivity, robustness and substrate adhesion. A
10 resist composition comprising the polymer as a base resin is
sensitive to high-energy radiation, has excellent
sensitivity, resolution, and etching resistance, and lends
itself to micropatterning with electron beams or deep-UV.



(1)